







# Plasma Discharge Undulator: a novel concept for plasma-based radiation sources

Poster ID: 716





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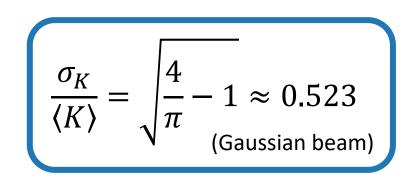
## INTRODUCTION

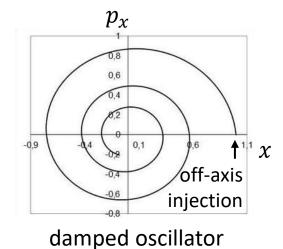
Plasma discharge devices have recently demonstrated their potential for compact particle beam manipulation. Building upon the Active Plasma Lens [1] and its extension to curved geometries (Active Plasma Bending [2]), new studies have revealed that chicane-like configurations can support sub-betatron oscillations of the beam. Motivated by this observation, the novel concept of the Plasma Discharge Undulator (PDU) is introduced. The PDU consists of a sequence of transversely displaced jointed plasma capillaries, carrying a high-current discharge. The resulting azimuthal magnetic field focuses the beam, while the periodic transverse displacement of the equilibrium axis acts as a geometric forcing term. This yields a well-defined oscillation at a wavelength  $\lambda_{PDU}$  distinct from the natural betatron wavelength  $\lambda_{\beta}$ . By proper injection, collective betatron oscillations can be suppressed, leaving only the forced  $\lambda_{PDU}$  beam centroid oscillation. This approach eliminates the intrinsic K-spread limitation of plasma undulators, achieving a narrow undulator strength distribution while preserving strong plasma focusing for beam matching. The theoretical framework, single-particle and beam dynamics analyses, first estimates of radiation emission from the PDU and preliminary particle-in-cell studies of segmented capillaries are presented. The PDU thus offers a pathway toward miniaturized, tunable, full-plasma-based radiation beamlines, with enhanced control over beam quality and radiation properties.

### **MOTIVATION**

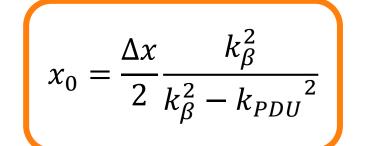
#### Betatronic plasma undulators limitations:

- On axis injection: **K-spread constraint**
- Off axis injection: less K-spread but possibly unstable + oscillation damping and/or emittance growth
- Possible solution? Add driving term How? **Geometrically**





# **ANALYTICAL MODEL: DRIVEN OSCILLATOR**



$$K_{PDU} = \frac{\gamma \Delta x}{2\frac{h}{\pi} - \frac{4m_e c \gamma}{e\mu_0 J} \frac{\pi}{h}}$$

$$\sigma_{M} = \left(\frac{2m_{e}c\gamma\epsilon_{rms}^{2}}{e\mu_{0}J}\right)^{\frac{1}{4}}$$

sub-oscillation amplitude

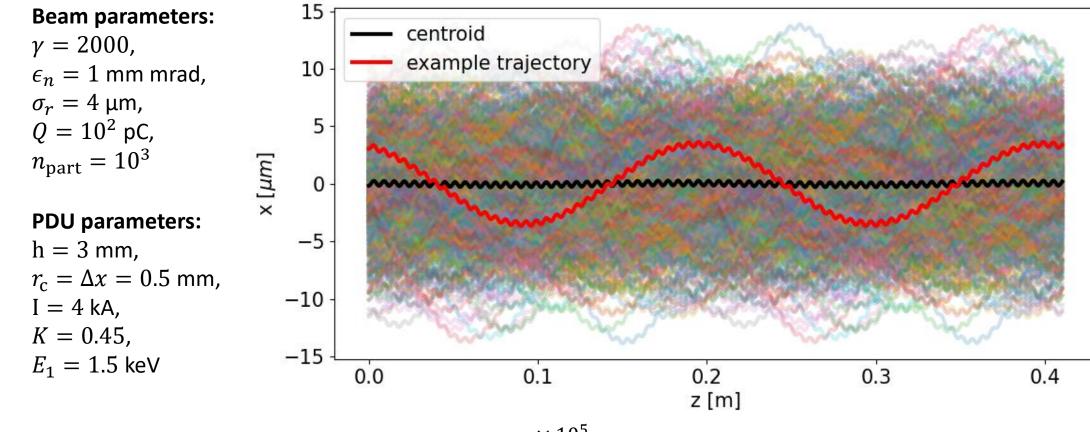
z [mm]

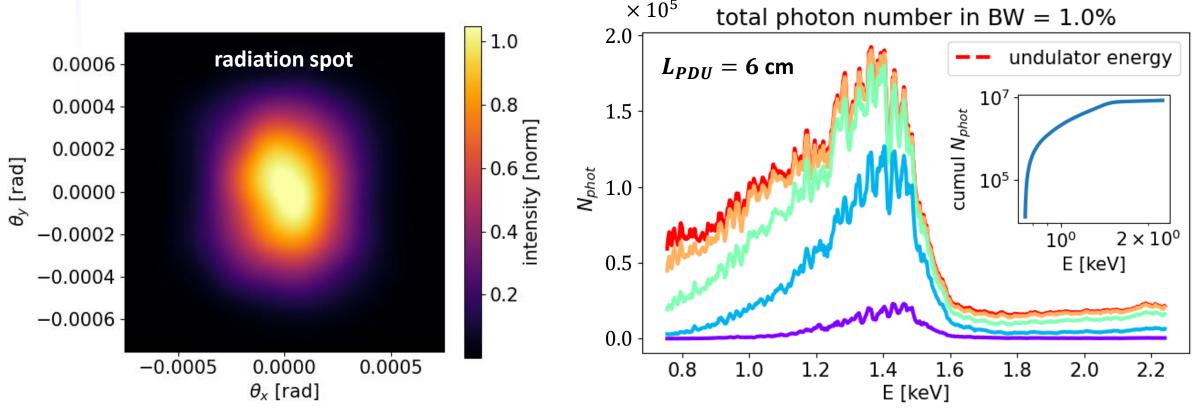
undulator strength

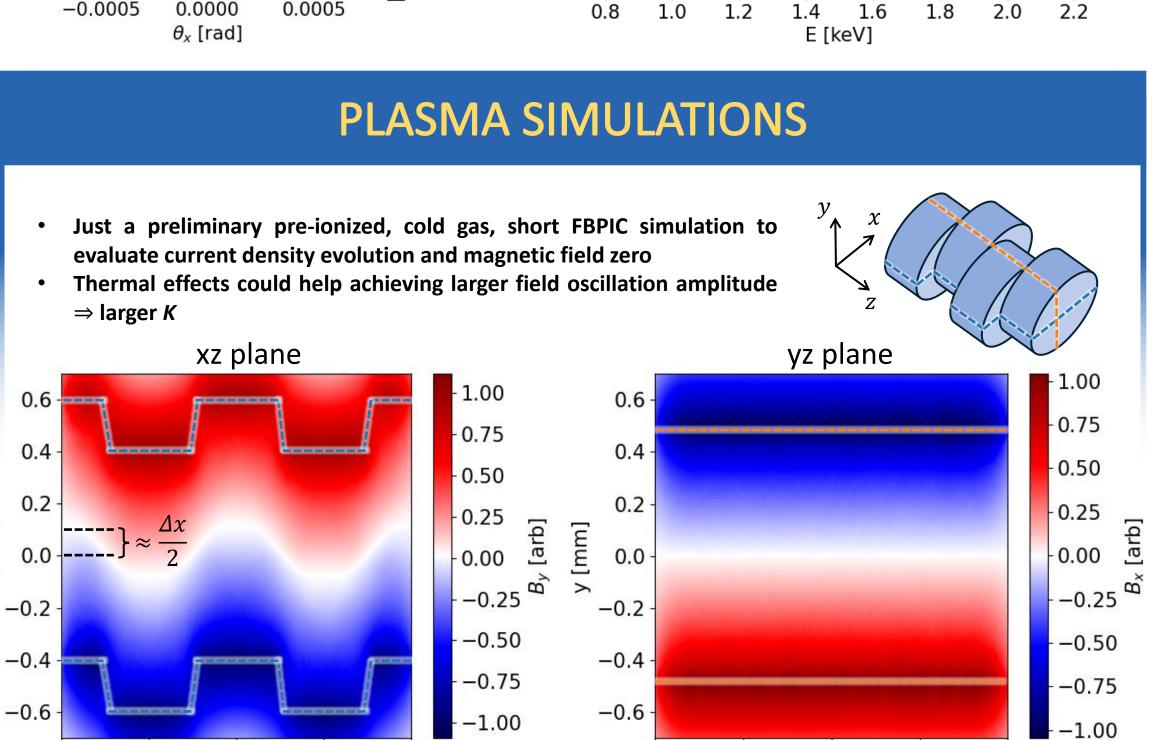
**APL** matching

# CONCEPT sapphire glass single capillary adjust the gap stack element capillary section: APL linear top view: plasma discharge O(kA)

# DYNAMICS AND RADIATION SIMULATIONS

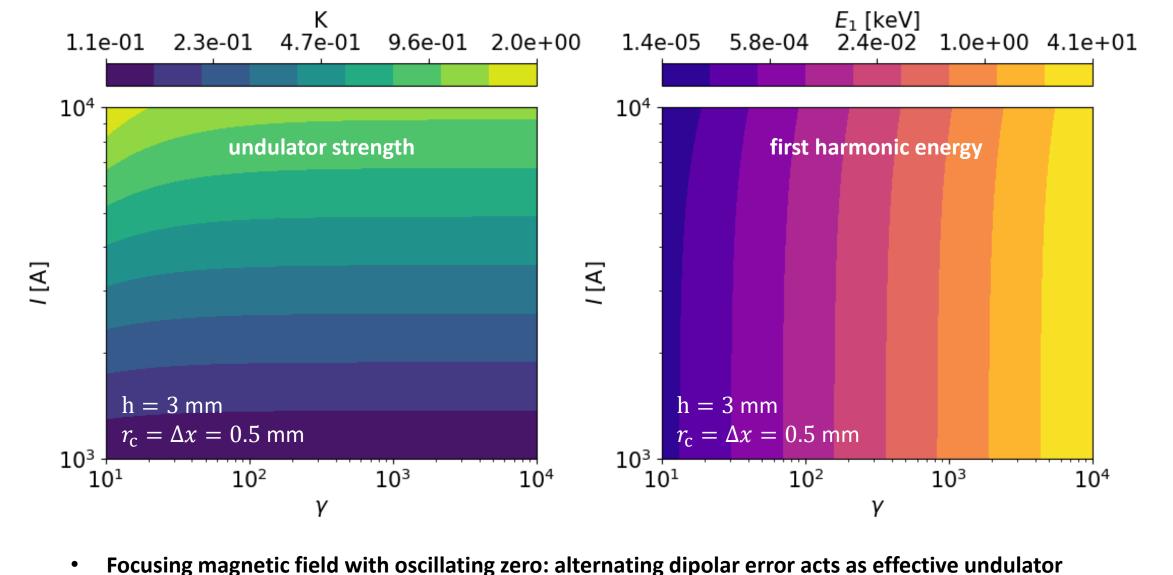






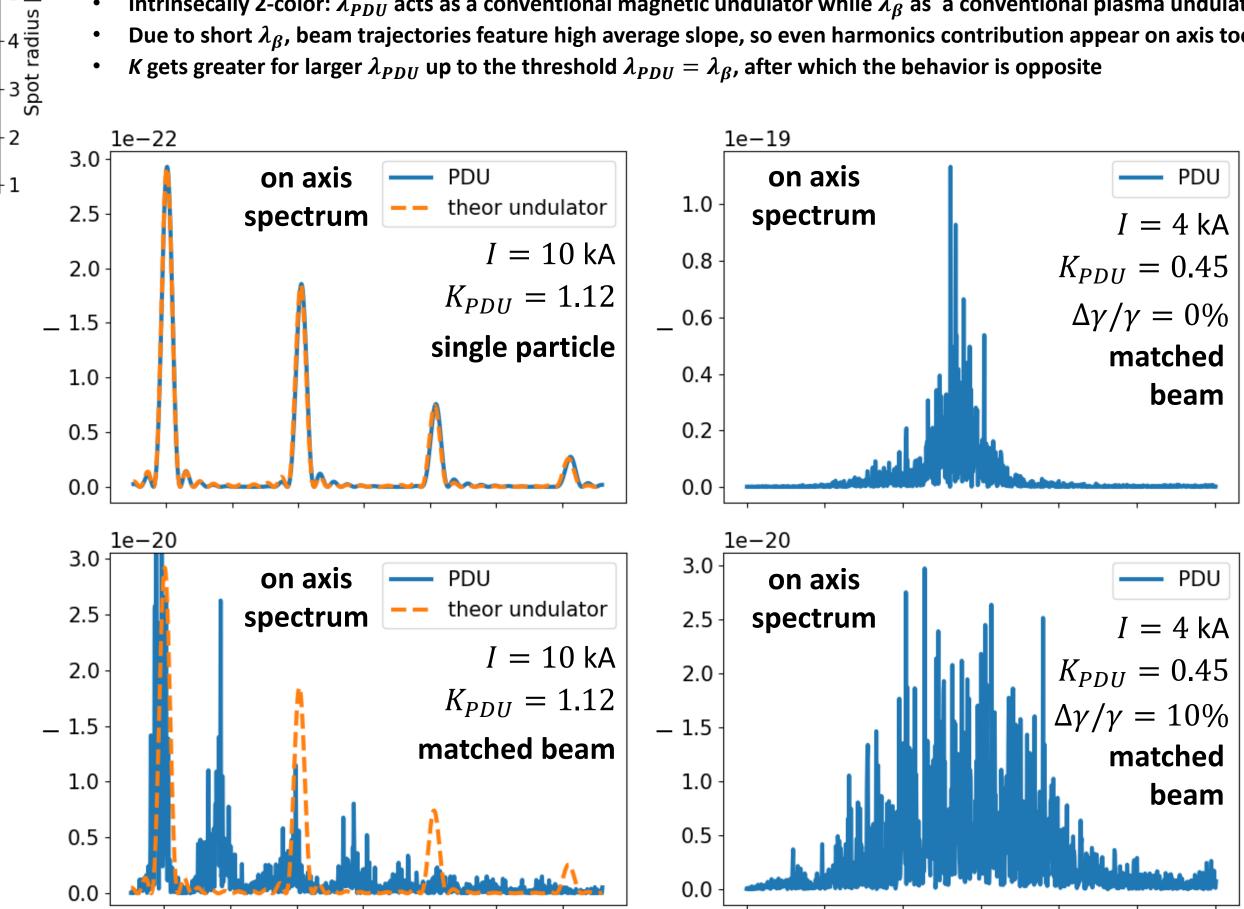
h = 1 mm,  $r_c = 0.5$  mm,  $\Delta x = 0.2$  mm,  $n_p = 10^{15}$  cm<sup>-3</sup>,  $E_z = 2.5 \times 10^5$  V/m,  $n_{modes} = 6$ 

z [mm]



focusing magnetic field

- Magnetic field driven bending: the beam should feature longitudinal microbunching (transverse in ICL) Beam centroid injection at  $x=x_0$  avoids  $\lambda_B$  collective oscillations, leaving just  $\lambda_{PDU}$  collective oscillations
  - The wavelength  $\lambda_{PDU}$  appears as a modulation of amplitude  $x_0$  over the main  $\lambda_{\beta}$  trajectory oscillation
  - Intrinsecally 2-color:  $\lambda_{PDU}$  acts as a conventional magnetic undulator while  $\lambda_{eta}$  as a conventional plasma undulator Due to short  $\lambda_{\beta}$ , beam trajectories feature high average slope, so even harmonics contribution appear on axis too
  - K gets greater for larger  $\lambda_{PDU}$  up to the threshold  $\lambda_{PDU} = \lambda_{\beta}$ , after which the behavior is opposite



[1] "Direct measurement of focusing fields in active plasma lenses", DOI: https://doi.org/10.1103/PhysRevAccelBeams.21.122801

1.00

0.75

1.25

1.75

1.50

E [keV]

2.00 2.25

E [keV]